

(12) INTERNATIONAL APPLICATION PUBLISHED UNDER THE PATENT COOPERATION TREATY (PCT)

(19) World Intellectual Property
Organization
International Bureau

(43) International Publication Date
28 September 2023 (28.09.2023)



(10) International Publication Number
WO 2023/180161 A3

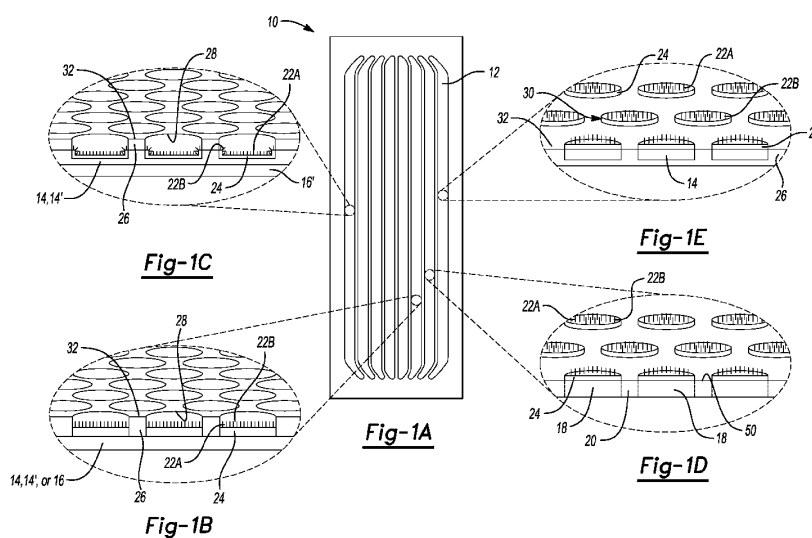
- (51) International Patent Classification:
G03F 7/00 (2006.01) *B01L 3/00* (2006.01)
- (21) International Application Number:
PCT/EP2023/056729
- (22) International Filing Date:
16 March 2023 (16.03.2023)
- (25) Filing Language: English
- (26) Publication Language: English
- (30) Priority Data:
63/322,584 22 March 2022 (22.03.2022) US
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(81) Designated States (*unless otherwise indicated, for every
kind of national protection available*): AE, AG, AL, AM,
AO, AT, AU, AZ, BA, BB, BG, BH, BN, BR, BW, BY, BZ,
CA, CH, CL, CN, CO, CR, CU, CV, CZ, DE, DJ, DK, DM,
DO, DZ, EC, EE, EG, ES, FI, GB, GD, GE, GH, GM, GT,
HN, HR, HU, ID, IL, IN, IQ, IR, IS, IT, JM, JO, JP, KE, KG,
KH, KN, KP, KR, KW, KZ, LA, LC, LK, LR, LS, LU, LY,
MA, MD, MG, MK, MN, MU, MW, MX, MY, MZ, NA,
NG, NI, NO, NZ, OM, PA, PE, PG, PH, PL, PT, QA, RO,
RS, RU, RW, SA, SC, SD, SE, SG, SK, SL, ST, SV, SY, TH,

(54) Title: METHODS FOR MAKING FLOW CELL SURFACES



(57) Abstract: In an example method, an initial depression is defined in a first resin layer of a multi-layer stack including the first resin layer over a second resin layer or a base support. The first resin layer is resistant to silanization in an organic solvent, the second resin layer or the base support is reactive toward silanization in the organic solvent, and the first resin layer and the second resin layer or the base support are orthogonally etchable. A remaining portion of the first resin layer at the initial depression is anisotropically etched, using air or O₂ plasma, through to expose a surface of the second resin layer or the base support and to form a depression. The multi-layer stack is exposed to a silane in the organic solvent to selectively silanizing the surface of the second resin layer or the base support at the depression.

[Continued on next page]

TJ, TM, TN, TR, TT, TZ, UA, UG, US, UZ, VC, VN, WS,
ZA, ZM, ZW.

- (84) Designated States** (*unless otherwise indicated, for every kind of regional protection available*): ARIPO (BW, CV, GH, GM, KE, LR, LS, MW, MZ, NA, RW, SC, SD, SL, ST, SZ, TZ, UG, ZM, ZW), Eurasian (AM, AZ, BY, KG, KZ, RU, TJ, TM), European (AL, AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HR, HU, IE, IS, IT, LT, LU, LV, MC, ME, MK, MT, NL, NO, PL, PT, RO, RS, SE, SI, SK, SM, TR), OAPI (BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, KM, ML, MR, NE, SN, TD, TG).

Published:

- with international search report (Art. 21(3))
- before the expiration of the time limit for amending the claims and to be republished in the event of receipt of amendments (Rule 48.2(h))
- with sequence listing part of description (Rule 5.2(a))

(88) Date of publication of the international search report:

02 November 2023 (02.11.2023)